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TO: Assistant Commissioner for Patents
Washington, D.C. 20231

FAX NO.: 703-308-7382

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KINDLY DIRECT THIS COMMUNICATION TO:

EXAMINER : M. Whipple
GROUP : 2813

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of:

HUI-JUNG WU, ET AL ✓

Docket : 30-4540 (4780)

Serial Number: 09/141,287 ✓

Group Art Unit: 2813

Filed: August 27, 1998 ✓

Examiner: M. Whipple

For: PROCESS FOR OPTIMIZING MECHANICAL STRENGTH
OF NANOPOROUS SILICA ✓AMENDMENT7/A
9-24-99
J ProctorAssistant Commissioner for Patents
Washington, D.C. 20231

Sir:

In response to the Office Action mailed June 22, 1999, please amend the above identified patent application as follows:

In the claims:

1. A process for forming a nanoporous dielectric coating on a substrate which comprises:

(a) forming a substantially uniform alkoxysilane gel composition on a surface of a substrate, which alkoxysilane gel composition comprises a combination of at least one alkoxysilane, an organic solvent composition, water, and an optional base catalyst;

wherein the organic solvent composition comprises a relatively high volatility solvent having a boiling point of about 120 °C or less, and a relatively low volatility solvent

selected from the group consisting of di(ethylene)glycol monomethyl ether,

tri(ethylene)glycol monomethyl ether, tetra(ethylene)glycol monomethyl ether,

di(propylene)glycol monomethyl ether, tri(propylene)glycol monomethyl ether, triethylene

glycol monomethyl ether, and mixtures thereof.

(b) heating the substrate for a sufficient time and at a sufficient temperature

in an organic solvent vapor atmosphere to thereby condense the gel composition; and

then

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